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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO	
10/643,896	08/20/2003	Nobuo Aoi	740819-1033	4663	
	7590 11/04/2004		EXAMINER		
NIXON PEABODY, LLP 401 9TH STREET, NW SUITE 900 WASHINGTON, DC 20004-2128			OLSEN, A	OLSEN, ALLAN W	
			ART UNIT	PAPER NUMBER	
WASHINGTO	1, DC 20004-2128		1763		
			DATE MAILED: 11/04/2004	,	

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)	
	10/643,896	AOI, NOBUO	A
Office Action Summary	Examiner	Art Unit	
	Allan Olsen	4700	
The MAILING DATE of this communication a	appears on the cover sheet w	vith the correspondence addi	220
			-
A SHORTENED STATUTORY PERIOD FOR REF THE MAILING DATE OF THIS COMMUNICATION - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a recommunication of the period for reply is specified above, the maximum statutory perions are period for reply within the set or extended period for reply will, by state Any reply received by the Office later than three months after the main earned patent term adjustment. See 37 CFR 1.704(b).	N. 1.136(a). In no event, however, may a eply within the statutory minimum of thind will apply and will expire SIX (6) MO	reply be timely filed irty (30) days will be considered timely. NTHS from the mailing date of this comm	nunication.
Status			
1) Responsive to communication(s) filed on 16	August 2004.		
2a) This action is FINAL . 2b) ⊠ Th	is action is non-final.		
3)☐ Since this application is in condition for allow	ance except for formal mat	ters, prosecution as to the m	erite ie
closed in accordance with the practice under	Ex parte Quayle, 1935 C.E). 11, 453 O.G. 213.	CIIIS IS
Disposition of Claims		,	
4)⊠ Claim(s) <u>1-18</u> is/are pending in the application	-		
4a) Of the above claim(s) <u>11-18</u> is/are withdra 5) Claim(s) is/are allowed.	iwn from consideration.		
6)⊠ Claim(s) <u>1-10</u> is/are rejected.			
7) Claim(s) is/are objected to.			
8) Claim(s) are subject to restriction and/	or election requirement.		
Application Papers			
9)☐ The specification is objected to by the Examina	or		
10) ☐ The drawing(s) filed on 20 August 2003 is/are:			
Applicant may not request that any objection to the	a) accepted or b) obj	ected to by the Examiner.	
Applicant may not request that any objection to the	drawing(s) be held in abeyan	ce. See 37 CFR 1.85(a).	
Replacement drawing sheet(s) including the correct	tion is required if the drawing(s) is objected to. See 37 CFR 1	.121(d).
11) The oath or declaration is objected to by the Ex	xaminer. Note the attached	Office Action or form PTO-1	52.
Priority under 35 U.S.C. § 119			
12)⊠ Acknowledgment is made of a claim for foreign a)⊠ All b)□ Some * c)□ None of:	priority under 35 U.S.C. §	119(a)-(d) or (f).	
1. Certified copies of the priority document	s have been received.		
2. Certified copies of the priority document	s have been received in An	inlication No. 00/402 944	
3. Copies of the certified copies of the prior	rity documents have been r	eceived in this National Ctar	
application from the International Bureau	(PCT Rule 17 2(a))	cocived in this National Stag	je
* See the attached detailed Office action for a list	of the certified copies not re	eceived	
	The sopies not re	505/VGQ.	
Attachment(s)			
Notice of References Cited (PTO-892)	4) Interview Sur	mmary (PTO-413)	
Notice of Draftsperson's Patent Drawing Review (PTO-948)	Paper No(s)/	Mail Date	
Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date 8/20/2003.	5) Notice of Info 6) Other:	ormal Patent Application (PTO-152)	
Patent and Trademark Office OL-326 (Rev. 1-04)	ッロ oliei	•	

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DETAILED ACTION

Election/Restrictions

Applicant's election of Group I, claims 1-10, in the reply filed August 16, 2004 is acknowledged. Because applicant did not distinctly and specifically point out the supposed errors in the restriction requirement, the election has been treated as an election without traverse (MPEP § 818.03(a)).

Claims 11-18 are withdrawn from further consideration pursuant to 37 CFR 1.142(b) as being drawn to a nonelected invention, there being no allowable generic or linking claim. Election was made without traverse the reply filed August 16, 2004.

Claim Rejections - 35 USC § 112

The following is a quotation of the first paragraph of 35 U.S.C. 112:

The specification shall contain a written description of the invention, and of the manner and process of making and using it, in such full, clear, concise, and exact terms as to enable any person skilled in the art to which it pertains, or with which it is most nearly connected, to make and use the same and shall set forth the best mode contemplated by the inventor of carrying out his invention.

Claims 1-10 are rejected under 35 U.S.C. 112, first paragraph, because the claims are broader in scope than the enabling disclosure. Specifically, claim 1 recites "a fluorine gas" which, given its broadest reasonable interpretation is taken to mean a fluorine containing gas. The specification, while being enabling for fluorine containing gases such as F2, HF, NF3, does not reasonably provide enablement for etching with a host compounds that are among the vast number of fluorine containing compounds. As such, the specification does not enable any person skilled in the art to which it pertains, or with which it is most nearly connected, to use the invention commensurate in scope

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with these claims. Similarly, claims 3 recites: "a hydrogen gas, a nitrogen gas and a fluorine gas" which is interpreted as meaning - a hydrogen containing gas, a nitrogen containing gas and a fluorine containing gas. Claim 5 recites "a hydrogen gas" which is interpreted as meaning - a hydrogen containing gas. Claim 7 recites "a nitrogen gas" which is interpreted as meaning - a nitrogen containing gas. Claim 9 recites "a nitrogen gas" which is interpreted as meaning - a nitrogen containing gas.

The following is a quotation of the second paragraph of 35 U.S.C. 112:

The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

Claims 1-10 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

Claims 1, 3, 5, 7 and 9 include limitations that recite the phrase "main constituents". The phrase "main constituent" renders the claim indefinite. Neither the specification nor the claim defined this phrase. Therefore, one of ordinary skill in the art would not be reasonably apprised of the scope of the invention.

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

⁽b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

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(e) the invention was described in a patent granted on an application for patent by another filed in the United States before the invention thereof by the applicant for patent, or on an international application by another who has fulfilled the requirements of paragraphs (1), (2), and (4) of section 371(c) of this title before the invention thereof by the applicant for patent.

Claims 3-6, 9 and 10 are rejected under 35 U.S.C. 102(b) as being anticipated by Japanese Patent Publication 10-268526 (hereinafter, Sato).

Sato teaches a method to anisotropically etch a silicon-containing organic film. Sato teaches using a plasma source gas comprising a fluorine-containing compound such as NF₃, F₂ or CF₄. Additionally Shinohara teaches providing N₂ and Ar to the etchant mixture. See, for example, machine translation paragraphs 0050 and 0059.

Claims 3-6, 9 and 10 are rejected under 35 U.S.C. 102(e) as being anticipated by U. S. Patent 6,207,583 issued to Dunne et al. (hereinafter, Dunne).

Dunne teaches a method to anisotropically etch a silicon-containing organic film. Sato teaches using a plasma source gas may comprising a fluorine containing compound such as NF₃, SF₆ or CF₄ in combination with N₂, H₂ and Ar. See: column 3, lines 30-38, 58, column 4, lines 2, 9-12; column 4, line 62 – column 5, line10; column 6, line 48 – column 7, line 12; column 7, line 62 – column 8, line 12; column 13.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

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Claims 1 and 2 are rejected under 35 U.S.C. 103(a) as being unpatentable over Dunne in view of U.S. Patent 6,350,670 issued to Andideh et al. (hereinafter, Andideh).

The teaching of Dunne, as noted above, is herein relied upon.

Dunne does not teach etching with NH₃.

Andideh teaches etching an organic/inorganic composite layer that is similar to the layer etched by Dunne. Andideh teaches etching with a mixture of H_2 and N_2 (forming gas). Andideh teaches that NH_3 may be used as an alternative to the using the forming gas mixture.

It would have been obvious to one skilled in the art to replace the forming gas mixture of Dunne with NH₃ because Andideh teaches that NH₃ and forming gas are functional equivalents with regard to the etching of an organic/inorganic composite.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Allan Olsen whose telephone number is 571-272-1441. The examiner can normally be reached on M-F 1-5.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Greg Mills can be reached on 571-272-1439. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

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Allan Olsen **Primary Examiner** Page 6

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